

Hiroyuki Nishinaka

List of Publications by Year in descending order

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48
papers

1,741
citations

331670

21
h-index

276875

41
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48
all docs

48
docs citations

48
times ranked

1513
citing authors

#	ARTICLE	IF	CITATIONS
1	Carrier concentration dependence of band gap shift in n-type ZnO:Al films. Journal of Applied Physics, 2007, 101, 083705.	2.5	380
2	Zno-based thin films synthesized by atmospheric pressure mist chemical vapor deposition. Journal of Crystal Growth, 2007, 299, 1-10.	1.5	160
3	Growth of Crystalline Zinc Oxide Thin Films by Fine-Channel-Mist Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2008, 47, 4669.	1.5	109
4	Carrier concentration induced band-gap shift in Al-doped Zn _{1-x} Mg _x O thin films. Applied Physics Letters, 2006, 89, 262107.	3.3	103
5	Linear-Source Ultrasonic Spray Chemical Vapor Deposition Method for Fabrication of ZnMgO Films and Ultraviolet Photodetectors. Japanese Journal of Applied Physics, 2006, 45, L857-L859.	1.5	87
6	Heteroepitaxial growth of $\hat{\mu}$ -Ga ₂ O ₃ thin films on cubic (111) MgO and (111) yttria-stabilized zirconia substrates by mist chemical vapor deposition. Japanese Journal of Applied Physics, 2016, 55, 1202BC.	1.5	84
7	Stoichiometric control for heteroepitaxial growth of smooth $\hat{\mu}$ -Ga ₂ O ₃ thin films on <i>c</i> -plane AlN templates by mist chemical vapor deposition. Japanese Journal of Applied Physics, 2017, 56, 078004.	1.5	68
8	Low-Temperature Growth of ZnO Thin Films by Linear Source Ultrasonic Spray Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2007, 46, 6811-6813.	1.5	65
9	Epitaxial growth of $\hat{\pm}$ -Ga ₂ O ₃ thin films on a-, m-, and r-plane sapphire substrates by mist chemical vapor deposition using $\hat{\pm}$ -Fe ₂ O ₃ buffer layers. Materials Letters, 2017, 205, 28-31.	2.6	63
10	Microstructures and rotational domains in orthorhombic $\hat{\mu}$ -Ga ₂ O ₃ thin films. Japanese Journal of Applied Physics, 2018, 57, 115601.	1.5	61
11	Heteroepitaxial growth of $\hat{\mu}$ -(Al _x Ga _{1-x}) ₂ O ₃ alloy films on <i>c</i> -plane AlN templates by mist chemical vapor deposition. Applied Physics Letters, 2018, 112, .	3.3	59
12	Incorporation of indium into $\hat{\mu}$ -gallium oxide epitaxial thin films grown <i>via</i> mist chemical vapour deposition for bandgap engineering. CrystEngComm, 2018, 20, 1882-1888.	2.6	54
13	Heteroepitaxial growth of single-phase $\hat{\mu}$ -Ga ₂ O ₃ thin films on <i>c</i> -plane sapphire by mist chemical vapor deposition using a NiO buffer layer. CrystEngComm, 2018, 20, 6236-6242.	2.6	38
14	Growth characteristics of single-crystalline ZnMgO layers by ultrasonic spray assisted mist CVD technique. Physica Status Solidi (B): Basic Research, 2010, 247, 1460-1463.	1.5	37
15	Rapid homoepitaxial growth of (010) $\hat{2}$ -Ga ₂ O ₃ thin films via mist chemical vapor deposition. Materials Science in Semiconductor Processing, 2021, 128, 105732.	4.0	35
16	Use of mist chemical vapor deposition to impart ferroelectric properties to $\hat{\mu}$ -Ga ₂ O ₃ thin films on SnO ₂ /c-sapphire substrates. Materials Letters, 2018, 232, 47-50.	2.6	26
17	Mist Chemical Vapor Deposition of Single-Phase Metastable Rhombohedral Indium Tin Oxide Epitaxial Thin Films with High Electrical Conductivity and Transparency on Various $\hat{\pm}$ -Al ₂ O ₃ Substrates. Crystal Growth and Design, 2018, 18, 4022-4028.	3.0	24
18	Single-Domain and Atomically Flat Surface of $\hat{\mu}$ -Ga ₂ O ₃ Thin Films on FZ-Grown $\hat{\mu}$ -GaFeO ₃ Substrates via Step-Flow Growth Mode. ACS Omega, 2020, 5, 29585-29592.	3.5	24

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19	Step-flow growth of homoepitaxial ZnO thin films by ultrasonic spray-assisted MOVPE. Journal of Crystal Growth, 2008, 310, 5007-5010.	1.5	23
20	Growth and characterization of F-doped $\hat{\mu}$ -Ga ₂ O ₃ thin films with low electrical resistivity. Thin Solid Films, 2019, 682, 18-23.	1.8	23
21	Thermodynamically metastable $\hat{\mu}$ -, $\hat{\mu}$ - (or $\hat{\nu}$ -), and $\hat{\nu}$ -Ga ₂ O ₃ : From material growth to device applications. APL Materials, 2022, 10, .	5.1	23
22	Solution-based mist CVD technique for CH ₃ NH ₃ Pb(Br) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 Applied Physics, 2016, 55, 100308.	1.5	21
23	Phase control of $\hat{\mu}$ - and $\hat{\nu}$ -Ga ₂ O ₃ epitaxial growth on LiNbO ₃ and LiTaO ₃ substrates using $\hat{\mu}$ -Fe ₂ O ₃ buffer layers. AIP Advances, 2020, 10, .	1.3	18
24	PEDOT:PSS/GaAs $\hat{\nu}$ -Bi organic-inorganic solar cells. Japanese Journal of Applied Physics, 2019, 58, 060907.	1.5	16
25	van der Waals epitaxy of ferroelectric $\hat{\mu}$ -gallium oxide thin film on flexible synthetic mica. Japanese Journal of Applied Physics, 2020, 59, 025503.	1.5	15
26	Impact of a small change in growth temperature on the tail states of GaAsBi. Journal of Applied Physics, 2019, 126, 045702.	2.5	14
27	Epitaxial growth of $\hat{\nu}$ -(Al _x Ga _{1-x}) ₂ O ₃ alloy thin films on spinel substrates via mist chemical vapor deposition. Journal of Alloys and Compounds, 2021, 851, 156927.	5.5	14
28	Plan-view TEM observation of a single-domain $\hat{\nu}$ -Ga ₂ O ₃ thin film grown on $\hat{\mu}$ -GaFeO ₃ substrate using GaCl ₃ precursor by mist chemical vapor deposition. Japanese Journal of Applied Physics, 2022, 61, 018002.	1.5	14
29	Deep levels and carrier capture kinetics in n-GaAsBi alloys investigated by deep level transient spectroscopy. Journal Physics D: Applied Physics, 2021, 54, 345109.	2.8	11
30	Epitaxial Growth of Bendable Cubic NiO and In ₂ O ₃ Thin Films on Synthetic Mica for p- and n-type Wide-Bandgap Semiconductor Oxides. MRS Advances, 2020, 5, 1671-1679.	0.9	9
31	Junction properties of nitrogen-doped ZnO thin films. Physica Status Solidi C: Current Topics in Solid State Physics, 2008, 5, 3088-3090.	0.8	8
32	Fabrication of a GaAs/GaNAsBi solar cell and its performance improvement by thermal annealing. Semiconductor Science and Technology, 2021, 36, 095020.	2.0	7
33	Alloying In ₂ O ₃ and Ga ₂ O ₃ on AlN templates for deep-ultraviolet transparent conductive films by mist chemical vapor deposition. Japanese Journal of Applied Physics, 2022, 61, SC1037.	1.5	6
34	Improving the photovoltaic properties of GaAs/GaAsBi pin diodes by inserting a compositionally graded layer at the hetero-interface. Semiconductor Science and Technology, 2022, 37, 065016.	2.0	6
35	Heteroepitaxial growth of $\hat{\mu}$ -Ga ₂ O ₃ thin films on cubic (111) GGG substrates by mist chemical vapor deposition. , 2017, , .		5
36	A preliminary study on mist CVD-derived ferroelectric Hf $\hat{\nu}$ -Zr _x O ₂ films featuring its possibility of suitable operation for non-volatile analog memory. Japanese Journal of Applied Physics, 2020, 59, SPPB09.	1.5	5

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37	Observing the microstructure of a (001) $\text{In}_2\text{Ga}_2\text{O}_3$ thin film grown on a (~ 201) $\text{In}_2\text{Ga}_2\text{O}_3$ substrate using automated crystal orientation mapping transmission electron microscopy. CrystEngComm, 2022, 24, 3239-3245.	2.6	5
38	Determination of Zn-containing sites in $\text{In}_2\text{Ga}_2\text{O}_3$ film grown through mist chemical vapor deposition via X-ray absorption spectroscopy. Japanese Journal of Applied Physics, 2020, 59, 070909.	1.5	4
39	Epitaxial growth of metastable c-plane rhombohedral indium tin oxide using mist chemical vapor deposition. Materials Science in Semiconductor Processing, 2022, 147, 106689.	4.0	4
40	Growth of indium-incorporated $\text{In}_2\text{Ga}_2\text{O}_3$ thin film lattice-matched to the $\mu\text{-GaFeO}_3$ substrate. Materials Letters: X, 2022, 14, 100149.	0.7	4
41	Mist Deposition Technique as a Green Chemical Route for Synthesizing Oxide and Organic Thin Films. Materials Research Society Symposia Proceedings, 2009, 1220, 4061.	0.1	3
42	Mist chemical vapor deposition study of 20 and 100 nm thick undoped ferroelectric hafnium oxide films on n+-Si(100) substrates. Japanese Journal of Applied Physics, 2019, 58, S11B10.	1.5	2
43	Growth of Metastable $\text{In}_2\text{Ga}_2\text{O}_3$; Epitaxial Thin Film on Flexible Synthetic Mica by Insertion $\text{In}_2\text{Fe}_2\text{O}_3$; Buffer Layer. Zairyo/Journal of the Society of Materials Science, Japan, 2021, 70, 738-744.	0.2	2
44	Fabrication OF ZnO and ZnMgO Thin Films and UV Photodetectors by Mist Chemical Vapor Deposition Method. Materials Research Society Symposia Proceedings, 2006, 957, 1.	0.1	1
45	Mist Chemical Vapor Deposition 2. Springer Series in Materials Science, 2020, , 243-255.	0.6	1
46	Ultrasonic spray assisted Mist-CVD method for high-quality crystalline and amorphous oxide semiconductors growth. Materials Research Society Symposia Proceedings, 2008, 1113, 1.	0.1	0
47	Microstructures of $\text{In}_2\text{Ga}_2\text{O}_3$ thin film on (100) TiO_2 substrate by mist chemical vapor deposition. , 2019, , .		0
48	Investigation of deep level defects in n-type GaAsBi. , 2022, , .		0